



2013 年國際平坦化會議 International Conference on Planarization/CMP Technology, ICPT 2013

新竹市國賓飯店新竹市中華路二段 188 號 10 樓

2013 Oct 30 ~ Nov1

活動網址: <http://www.icpt2013.ntust.edu.tw>

主辦單位：國立台灣科技大學晶圓平坦化創新研究中心、台灣平坦化應用技術協會

協辦單位：國立台灣中正大學前瞻製造系統頂尖研究中心、國立台灣清華大學

贊助單位：行政院國家科學委員會

探討化學機械研磨平坦化—使電子元件更小、更快、更多功能、更省電之關鍵製程

60 多名來自世界各地的產學專家，將發表半導體關鍵製程：化學機械研磨/平坦化相關議題。此製程是要使晶圓達到全面化的平坦 Global Planarization，俾使電子元件發揮極致功能。全球的平坦化也意味全球平坦化專業人士建立無障礙，暢通無阻的交流平台，使更前瞻、深遠的平坦化技術得以進深，且能在短期有更新更廣更符合經濟效益之應用。

專題涵蓋：

CMP for Frontier Device Process
Advanced CMP Process Development
CMP Process Control and Detection
CMP Consumables Development
CMP Consumables Characterization, Inspection, and Management
CMP Theory and Modeling
CMP 3D-IC Related Emergent Technologies
CMP for Non-Si IC
CMP consumables Delivery and Recycling
Enabling Technology for CMP

特約講員 Keynote Speakers (K):

K1: Dr. Yongsik Moon, Sr. Manager, CMP/Plating, GLOBALFOUNDRIES

K2: Dr. John Lau, Fellow, EOL, ITRI

K3: Dr. SV. Babu, Professor of Clarkson University

邀請講員 Invited Speakers (S):

S1: Dr. Katia Devriendt, CMP and Thinning Group of the Unit Process and Module Division, IMEC

S2: Dr. Hsin-Hsien Lu, Manager, R &D, TSMC

S3: Dr. Bo Un Yoon, Master, Process Development Team, Semiconductor R&D Center, Samsung Electronics Co.

S4: Dr. Manabu Tsujimura, CTO & President, Precision Machinery Company, EBARA Corporation

S5: Professor Weili Liu, Shanghai Institute of Microsystem and Information Technology

議程(會作微調)

Oct 30/Wed		Oct 31/Thu		Nov 1/Fri	
07:50	Sign-in	07:50	Sign-in	07:50	Sign-in
08:30-08:40	Opening Remark	08:30-09:00	Plenary 2 K2	08:30-09:00	Plenary 3 K3
08:40-09:10	Plenary 1 K1	09:00-10:05	Oral Session O6 Invited S3	09:00-10:00	Oral Session O10
09:10-09:25	Announcement ICPT 2014 Preview	10:05-10:30	Coffee break	10:00-10:25	Coffee Break and Exhibition
09:25-09:45	Coffee Break	10:30-11:15	Oral Session O7	10:25-11:30	Oral Session O11 Invited S5
09:45-10:30	Oral Session O1	11:15-11:40	Coffee break	11:30-13:10	Lunch Break and Exhibition
10:30-10:50	Coffee Break	11:40-12:25	Oral Session O8	13:10-13:55	Poster Session P3
10:50-12:10	Oral O2 Invited S1	12:25-13:45	Lunch break & Exhibition	13:55-14:30	Poster Display and Exhibition
12:10-13:40	Lunch break	13:45-14:50	Oral Session O9 Invited S4	14:30-15:40	Special Application Session
13:40-14:30	Oral Session O3 Invited S2	14:50-15:15	Coffee break	15:40-15:50	Coffee Break and Exhibition
14:30-14:50	Coffee Break and Exhibition	15:15-16:00	Poster Session P1	15:50-16:00	Best Poster Award
14:50-15:35	Oral Session O4	16:00-16:30	Poster Display and Exhibition	15:30-16:00	*Lucky Drawing Result 抽獎揭曉
15:35-16:00	Coffee Break	16:30-17:00	Poster Session P2	16:00-16:10	Closing Remark
16:00-17:15	Oral Session O5	17:00-17:30	Poster Display and Exhibition	*Stay till last moment to take "Lucky Drawing." Award will be something like IPAD.	
		18:30	Banquet		

費用 (台幣)	Oct 25 前		Oct 26-28	
	3 整天	單日	3 整天	單日
(A) 一般人士	15000	6000	15750	6000
(B) ICPT 國際委員	7500	4500	8250	4500
(C) 學生	3000	1800	3600	1800

➢ 3 整天報名(A)和(B) 含 3 日午餐，Oct 31 晚宴，大會論文集；(C) 含 3 日午餐，大會論文集
 ➢ 單日含當日午餐，不含 Oct 31 晚宴，不含大會論文集。單購大會論文集 700 元
 ➢ 僅參加 Oct 31 晚宴 2100 元